

INFORMATION DISCLOSURE CITATION IN AN APPLICATION (PTO-1449)			ATTY. DOCKET NO. 43889-951		SERIAL NO. (Divisional of Serial No. 08/965,892) <i>07/610,440</i>		
			APPLICANT Koji ERIGUCHI, et al.				
			FILING DATE July 05, 2000		GROUP 2825		
U.S. PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE	
<i>CME</i>	4,652,757	3/87	Carver	-	-	-	
<i>CME</i>	4,750,822	6/88	Rosencwaig et al.	-	-	-	
<i>CME</i>	5,260,772	11/93	Pollak et al.	-	-	-	
<i>CME</i>	5,536,936	7/96	Drevillon et al.	-	-	-	
<i>CME</i>	4,211,488	7/80	Kleinknecht	-	-	-	
<i>CME</i>	5,365,334	11/15/94	Bottka	-	-	-	
<i>CME</i>	5,379,109	1/3/95	Gaskill et al.	-	-	-	
<i>CME</i>	5,313,044	5/17/94	Massoud et al.	-	-	-	
<i>CME</i>	5,314,831	5/24/94	Hirae et al.	-	-	-	
<i>CME</i>	5,663,657	9/2/97	Lagowski et al.	-	-	-	
FOREIGN PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
<i>CME</i>	0655620	11/29/94	Europe	-	-		
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)							
<i>CME</i>	"Supervisory Run-To-Run Control of Polysilicon Gate Etch Using In Situ Ellipsometry", by Butlers et al., IEEE Transaction on Semiconductor Manufacturing, Vol. 7, No. 2, May 1, 1995, pp. 193-201.						
<i>CME</i>	"Measurement of Damage Profile in Semiconductors: A Sensitive Optical Technique", by Shwe et al., Applied Physics Letters, Vol. 62, No. 5, February 1, 1993, pp. 516-518.						
EXAMINER <i>C. Lushak</i>				DATE CONSIDERED <i>7-31-02</i>			

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.